

ABSTRACT OF THE DISCLOSURE

An optical multilayer structure material has a structure such that, on a substrate, a conductive layer
5 in contact with the substrate, a gap portion having a size that enables an interference phenomenon to occur and can be changed, and an optical thin film are formed in this order. The circumference of a movable portion in the optical thin film is uniformly supported by
10 supporting portions, suppressing generation of strain due to an internal stress. Through holes are formed in the movable portion to allow an etchant to easily reach a sacrifice layer when forming a gap portion by etching for sacrifice layer. There is provided an optical multilayer
15 structure material having a simple construction, which can suppress generation of strain due to an internal stress and can be advantageously used in an image display apparatus.